

ABSTRACT

Method of measuring focus of a lithographic projection apparatus

A method of measuring focus of a lithographic projection apparatus includes exposure of a photoresist covered test substrate with a plurality of verification fields. Each of the verification fields includes a plurality of verification markers, and the verification fields are exposed using a predetermined focus offset FO. After developing, an alignment offset for each of the verification markers is measured and translated into defocus data using a transposed focal curve. The method according to the invention results in a focus-versus alignment shift sensitivity some 50 times higher (typically $dX,Y/dZ = 20$) than the present LVT.

[Fig. 2]